

# Hamburg model [1]

$$\Delta N_{eff}(\Phi, t) = N_C(\Phi) + N_a(\Phi, t, T) + N_Y(\Phi, t, T)$$

Donor removal & Stable acceptor	$N_C(\Phi) = N_{C0}(1 - e^{-c\Phi}) - g_C\Phi$	
Unstable acceptor	$N_a(\Phi, t, T) = -g_a\Phi \exp(-\Theta(T)_a t / \tau_a), \quad \Theta(T)_a = \exp\left(\frac{E_a}{k_B}[1/T_R - 1/T]\right)$	
Reverse annealing	$N_Y(\Phi, t, T) = -g_y\Phi(1 - 1/(1 + \Theta(T)_y t / \tau_y)), \quad \Theta(T)_y = \exp\left(\frac{E_y}{k_B}[1/T_R - 1/T]\right)$	
Parameters	<p>Standard Silicon</p> $N_{C0} = 0.70 \times N_{eff,0}$ $c = 0.075 \text{ cm}^{-1} / N_{C0}$ $g_a = 0.018 \text{ cm}^{-1}$ $\tau_a = 2.29 \text{ days } (20^\circ\text{C} \equiv T_R)$ $E_a = 1.09 \text{ eV}$ $g_C = 0.017 \text{ cm}^{-1}$ $g_y = 0.059 \text{ cm}^{-1}$ $\tau_y = 480 \text{ days } (20^\circ\text{C})$ $E_y = 1.33 \text{ eV}$ $N_{eff,0} = 1.026 \times 10^{12} \text{ cm}^{-3}$	<p>Oxygenated Silicon</p> $N_{C0} = 0.45 \times N_{eff,0}$ $c = 0.075 \text{ cm}^{-1} / N_{C0} \quad (??)$ $g_a = 0.014 \text{ cm}^{-1}$ $\tau_a = 2.917 \text{ days } (20^\circ\text{C} \equiv T_R)$ $E_a = 1.09 \text{ eV}$ $g_C = 0.020 \text{ cm}^{-1}$ $g_y = 0.048 \text{ cm}^{-1}$ $\tau_y = 800 \text{ days } (20^\circ\text{C})$ $E_y = 1.33 \text{ eV}$ $N_{eff,0} = 1.026 \times 10^{12} \text{ cm}^{-3}$

[1] G. Lindstrom et al., NIM A 466(2001) 308-326